## (19) World Intellectual Property Organization International Bureau





(43) International Publication Date 24 February 2005 (24.02.2005)

**PCT** 

## (10) International Publication Number WO 2005/017624 A1

(51) International Patent Classification<sup>7</sup>: G03F 7/20

(21) International Application Number:

PCT/IB2004/051360

(22) International Filing Date: 2 August 2004 (02.08.2004)

(25) Filing Language:

English

(26) Publication Language:

English

(30) Priority Data: 03102518.2

13 August 2003 (13.08.2003) EP

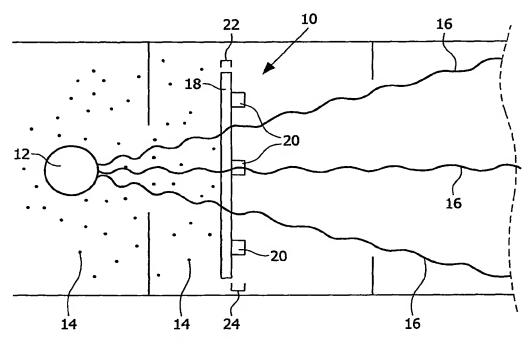
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- (81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.
- (84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM,

[Continued on next page]

(54) Title: FILTER FOR RETAINING A SUBSTANCE ORIGINATING FROM A RADIATION SOURCE AND METHOD FOR THE MANUFACTURE OF THE SAME



(57) Abstract: The invention describes a method of manufacturing a filter for retaining a substance originating from a radiation source, which filter comprises a thin layer that is transparent to extreme ultraviolet and/or soft X-ray radiation and which may be used inter alia in a device for EUV lithography. It is proposed that the filter (10) is high-temperature-resistant so as to render possible its use in particular for high-power radiation sources.

## WO 2005/017624 A1



ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

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## Published:

with international search report